

Dry Processing Workshop

With Uni Stuttgart/ZAQuant and IMS CHIPS

Tuesday 24th & Wednesday 25th September 2024

Tuesday 24th - Plasma Processing Day

TIME	TOPIC	SPEAKER
09:00 - 09:30	WELCOME COFFEE & REGISTRATION	
09:30 - 10:00	How do I treat my plasma system well?	Dr Owain Thomas, Oxford Instruments Plasma Technology
10:00 - 10:15	Uni Stuttgart/ZAQuant: Introductory presentation	Dr. Rainer Stöhr, University of Stuttgart/ZAQuant
10:15 - 10:30	IMS CHIPS: Introductory presentation	Dr. Mathias Kaschel, IMS CHIPS
10:30 - 11:00	COFFEE BREAK	
11:00 - 11:45	III/V, II/VI etch process: Understanding process trends to improve device performance	Dr Colin Welch, Oxford Instruments Plasma Technology
11:45 - 12:15	Dry etching of GaN-devices for power electronics and patterning using MEMS processes	Matthias Moser & Dr Martin Siebert, IMS CHIPS
12:15 - 13:00	Ion Beam Etching: IBE, RIBE, CAIBE	Dr Sebastien Pochon, Oxford Instruments Plasma Technology
13:00 - 14:00	LUNCH BREAK	
14:00 - 14:30	SiC plasma processing	Dr Matthew Loveday, Oxford Instruments Plasma Technology
14:30 - 15:00	How to use end point detection techniques to monitor and control plasma processes	Dr Matthew Loveday & Dr Owain Thomas, Oxford Instruments Plasma Technology
15:00 - 16:00	Low and high rate PECVD, end-pointing and advanced plasma cleaning	Dr Owain Thomas, Oxford Instruments Plasma Technology
16:00 - 16:30	Modern approaches for deep Si etching	Dr Colin Welch, Oxford Instruments Plasma Technology
16:30 - 18:00	Poster Session/Lab Tours	
19:00	Reception/Dinner	

Dry Processing 2 Day Workshop

With Uni Stuttgart/ZAQuant and IMS CHIPS

Tuesday 24th & Wednesday 25th September 2024

Wednesday 25th - Atomic Scale Processing Day

TIME	TOPIC	SPEAKER
09:00 - 09:30	WELCOME COFFEE & REGISTRATION	
09:30 - 10:00	Plasma ALD: how to use it and what it does	Dr Aileen O'Mahony, Oxford Instruments Plasma Technology
10:00 - 10:30	Atomic Layer Etching (ALE) Review	Dr Matthew Loveday, Oxford Instruments Plasma Technology
10:30 - 11:00	Atomic layer processing with enhanced endpoint solution enabling next generation GaN HEMTs	Dr Aileen O'Mahony, Oxford Instruments Plasma Technology
11:00 - 11:30	COFFEE BREAK	
11:30 - 12:00	Advanced Endpoint Products Enabling Critical Plasma Etch Processing Solutions	Dr Anthony Martinez, LayTec
12:00 - 12:30	ALD and ALE for quantum	Dr Nick Chittock, Oxford Instruments Plasma Technology
12:30 - 13:00	Temperature-dependent antibunching, PL and Raman measurements of NV centers in diamond	Dr Thomas Dieing, Oxford Instruments WITec
13:00 - 14:00	LUNCH BREAK	
14:00 - 14:30	Quantum optics with a spin	Prof. Dr Jörg Wrachtrup, ZAQuant
14:30 - 15:00	Wafer-scale growth of graphene and MoS ₂ and its encapsulation by ALD	Dr Sarah Riazimehr, Oxford Instruments Plasma Technology
15:00 - 15:30	Dry etching of Silicon and Silicon Nitride waveguides using electron beam lithography	Marcus Greul, IMS CHIPS
15:30 - 16:00	COFFEE BREAK	
16:00 - 16:30	LiNbO ₃ etching for quantum applications or Endpoint Detection techniques	Dr Colin Welch, Oxford Instruments Plasma Technology
16:30 - 17:00	Ion Beam Deposition	Dr Sebastien Pochon, Oxford Instruments Plasma Technology